



(43) 国際公開日
2008 年 5 月 15 日 (15.05.2008)

PCT

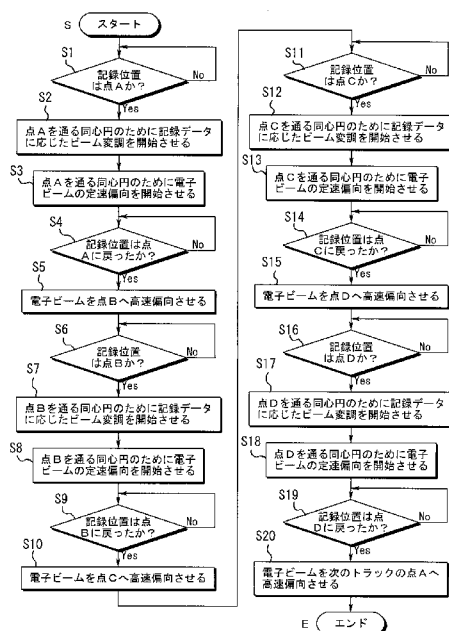
(10) 国際公開番号
WO 2008/056400 A1

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| (51) 国際特許分類:
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| (22) 国際出願日: 2006 年 11 月 6 日 (06.11.2006) | |
| (25) 国際出願の言語: 日本語 | |
| (26) 国際公開の言語: 日本語 | |

[続葉有]

(54) Title: METHOD FOR PRODUCING DISC MASTER

(54) 発明の名称: ディスク原盤製造方法



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5 START
S1 RECORDING POSITION IS POINT A ?
S2 START BEAM MODULATION ACCORDING TO RECORDING DATA FOR
CONCENTRIC CIRCLE PASSING POINT A
S3 START CONSTANT SPEED DEFLECTION OF ELECTRON BEAM FOR
CONCENTRIC CIRCLE PASSING POINT A
S4 RECORDING POSITION RETURNED TO POINT A ?
S5 DEFLECT ELECTRON BEAM TO POINT B AT HIGH SPEED
S6 RECORDING POSITION IS POINT B ?
S7 START BEAM MODULATION ACCORDING TO RECORDING DATA FOR
CONCENTRIC CIRCLE PASSING POINT B
S8 START CONSTANT SPEED DEFLECTION OF ELECTRON BEAM FOR
CONCENTRIC CIRCLE PASSING POINT B
S9 RECORDING POSITION RETURNED TO POINT B ?
S10 DEFLECT ELECTRON BEAM TO POINT C AT HIGH SPEED
S11 RECORDING POSITION IS POINT C ?
S12 START BEAM MODULATION ACCORDING TO RECORDING DATA FOR
CONCENTRIC CIRCLE PASSING POINT C
S13 START CONSTANT SPEED DEFLECTION OF ELECTRON BEAM FOR
CONCENTRIC CIRCLE PASSING POINT C
S14 RECORDING POSITION RETURNED TO POINT C ?
S15 DEFLECT ELECTRON BEAM TO POINT D AT HIGH SPEED
S16 RECORDING POSITION IS POINT D ?
S17 START BEAM MODULATION ACCORDING TO RECORDING DATA FOR
CONCENTRIC CIRCLE PASSING POINT D
S18 START CONSTANT SPEED DEFLECTION OF ELECTRON BEAM FOR
CONCENTRIC CIRCLE PASSING POINT D
S19 RECORDING POSITION RETURNED TO POINT D ?
S20 DEFLECT ELECTRON BEAM TO POINT A OF NEXT TRACK AT HIGH SPEED
E END

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**(57) Abstract:** A method for producing a disc master in which a master is rotary driven at a constant linear speed and moved in plane at such a constant speed as ensuring a predetermined moving amount per revolution of the master in a predetermined radial direction, an electron beam is deflected in the plane movement direction of the master by a first deflection amount per revolution of the master on the surface of the master on exposure of each concentric data pattern at first through (n-1)th round of each of a plurality of tracks, the electron beam is deflected in the direction opposite to the plane movement direction of the master by a second deflection amount on the surface of the master upon completion of exposure of concentric data pattern at first through (n-1)th round, and the electron beam is deflected in the direction opposite to the plane movement direction of the master by a third deflection amount on the surface of the master upon completion of exposure of concentric data pattern at the n-th round such that the irradiating position of electron beam is located at the exposure starting position of the concentric circle at the first round of adjacent track.

(57) 要約: 原盤を線速度一定で回転駆動し、原盤の1回転当たり所定の移動量となる定速度で原盤を所定半径方向に平面移動させ、複数のトラック各々の1周目～(n-1)周目各々の同心円のデータパターンへの露光において原盤の表面上で原盤の1回転当たり第1偏向量だけ電子ビームを原盤の平面移動方向に偏向させ、1回目～(n-1)周目各々の同心円のデータパターンの露光が終了すると、原盤の表面上で第2偏向量だけ電子ビームを原盤の平面移動方向とは逆方向に偏向させ、n周目の同心円のデータパターンの露光が終了すると、電子ビームの照射位置が隣接トラックの1周目の同心円の露光開始位置に位置するように原盤の表面上で第3偏向量だけ電子ビームを原盤の平面移動方向とは逆方向に偏向させるディスク原盤製造方法。



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(81) 指定国 (表示のない限り、全ての種類の国内保護  
が可能): AE, AG, AL, AM, AT, AU, AZ, BA, BB, BG,  
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SL, SM, SV, SY, TJ, TM, TN, TR, TT, TZ, UA, UG, US,  
UZ, VC, VN, ZA, ZM, ZW.

(84) 指定国 (表示のない限り、全ての種類の広域保護が可  
能): ARIPO (BW, GH, GM, KE, LS, MW, MZ, NA, SD,  
SL, SZ, TZ, UG, ZM, ZW), ユーラシア (AM, AZ, BY,  
KG, KZ, MD, RU, TJ, TM), ヨーロッパ (AT, BE, BG,  
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IS, IT, LT, LU, LV, MC, NL, PL, PT, RO, SE, SI, SK, TR),  
OAPI (BF, BJ, CF, CG, CI, CM, GA, GN, GQ, GW, ML,  
MR, NE, SN, TD, TG).

添付公開書類:

— 国際調査報告書